

APR 15 2003

Sheet 1 of 1

U.S. Department of Commerce, Patent and Trademark		Atty Docket No.	Application No.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		LUXT.118US1	09/577,795
		Applicant(s)	
(Use several sheets if necessary)		Charles W. Schietinger et al.	
		Filing Date	Group
		May 24, 2000	2877

## U.S. Patent Documents

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
<i>QW</i>	1	5,825,495	Oct. 20, 1998	Huber	<i>11</i>	<i>11</i>	
<i>QW</i>	2	5,828,460	Oct. 27, 1998	Lucovsky et al.	<i>11</i>	<i>11</i>	

## Foreign Patent Documents

							Translation	
		Document	Date	Country	Class	Subclass	Yes	No

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)


Examiner

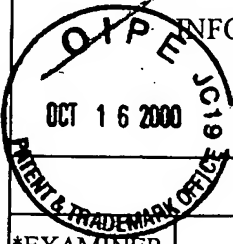

*[Signature]*

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FORM PT01449 (REV. 8-83)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. LUXT.118US1		SERIAL NO. 09/577,795					
<div style="display: flex; align-items: center; justify-content: center;"> <div style="text-align: center;">  </div> <div style="margin-left: 20px;"> <b>INFORMATION DISCLOSURE STATEMENT</b>  <i>(Use several sheets if necessary)</i> </div> </div>				APPLICANT Charles W. Schietinger et al.							
				FILED May 24, 2000		GROUP 2878					
<b>U. S. PATENT DOCUMENTS</b>											
*EXAMINER INITIAL		DOCUMENT NUMBER				DATE	NAME	CLASS	SUB CLASS	FILING DATE	
[Signature]	A1	4	2	9	3	2	2	4	10/06/1981	Gaston et al.	
	A2	5	1	6	6	0	8	0	11/24/1992	Schietinger et al.	
	A3	Re	3	4	4	2	5		11/02/1993	Schultz	
	A4	5	3	0	8	4	4	7	5/03/1994	Lewis et al.	
	A5	5	4	3	3	6	5	1	7/18/1995	Lustig et al.	
	A6	5	4	8	6	7	0	1	1/23/1996	Norton et al.	
	A7	5	5	6	4	8	3	0	10/15/1996	Böbel et al.	
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	A9	5	6	0	9	5	1	1	3/11/1997	Moriyama et al.	
	A10	5	7	2	4	1	4	4	3/03/1998	Muller et al.	
[Signature]	A11	5	7	6	9	5	4	0	6/23/1998	Schietinger et al.	
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		DOCUMENT NUMBER				DATE	COUNTRY	CLASS	SUB CLASS	TRANS.? (YES/NO)	
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	B2	6	2	1	9	0	7	2	8A	8/20/1987	Derwent Publ.-Japanese Abstract
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	B4	0	8	3	3	9	9	8	2	12/24/1996	Japanese Patent Office
[Signature]	B5	0	3	5	2	7	4	0	B1	5/01/1996	European Patent Specification
<b>OTHER DOCUMENTS</b> <i>(Including Author, Title, Date, Pertinent pages, Etc.)</i>											
[Signature]	C1	Williams, C.S. et al., "Emissivity, Reflectance, Absorptance, and Transmittance," <u>OPTICS: A Short Course for Engineers &amp; Scientists</u> , pps. 31-35, (1984)									
	C2	Litvak, H.E. et al., "Implementing Real-Time Endpoint Control in CMP," <u>Semiconductor International</u> , Vol. 19, No. 8, pps. 259-264 (July 1996)									
[Signature]	C3	Schietinger C., "Wafer Temperature Measurement in RTP," <u>F. Roozeboom (ed.), Advances in Rapid Thermal and Integrated Processing</u> , pps. 103-123, (1996) Kluwer Academic Publishers. Printed in the Netherlands									
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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
<i>OK</i>	A12 5 8 3 5 2 2 5	11/10/1998	Thakur			
	A13 5 8 3 8 4 4 7	11/17/1998	Hiyama et al.			
	A14 5 8 3 8 4 4 8	11/17/1998	Aiyer et al.			
	A15 5 8 5 1 1 3 5	12/22/1998	Sandhu et al.			
	A16 5 8 7 2 6 3 3	2/16/1999	Holzappel et al.			
	A17 5 8 9 9 7 9 2	5/04/1999	Yagi			
	A18 5 4 1 6 5 9 4	5/16/1995	Gross et al.			
	A19 5 4 9 9 7 3 3	3/19/1996	Litvak			
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DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANS.? (YES/NO)
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<i>OK</i>	C4	Schietinger, C., "Wafer Emissivity in RTP," F. Roozeboom (ed.), <u>Advances in Rapid Thermal and Integrated Processing</u> , pps. 125-141, (1996) Kluwer Academic Publishers, Printed in the Netherlands
	C5	Fang, S.J. et al., "Control of Dielectric Chemical Mechanical Polishing (CMP) Using an Interferometry Based Endpoint Sensor," <u>Proceedings of the IEEE 1998 International Inconnect Technology Conference</u> , Hyatt Regency Hotel, San Francisco, CA, pps. 98-76 to 98-78 (June 1-3, 1998)
	C6	Bibby, T. et al., "Endpoint Detection for CMP," <u>Journal of Electronic Materials</u> , Vol. 27, No. 10, pps. 1073 - 1081 (1998)
<i>OK</i>	C7	Berman, M. et al., "Review of In Situ & In-line Detection for CMP Applications," <u>Semiconductor Fabtech - 8th Edition</u> , Article contains eight pages.

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
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*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
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	A22 5 6 4 0 2 4 2	6/17/1997	O'Boyle et al.			
	A23 5 6 6 3 7 9 7	9/02/1997	Sandhu			
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	A27 5 2 9 2 6 0 5	3/08/1994	Thomson			
	A28 5 3 6 2 9 6 9	11/08/1994	Glenn			
	A29 5 6 9 5 6 6 0	12/09/1997	Litvak			
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	C8	Xu, H., et al., "Emissivity of Rough Silicon Surfaces: Measurement and Calculations," <u>Materials Research Society</u> , Symposium Proceedings Volume 387, symposium held April 17-20, 1995 - San Francisco, California, pps. 29-34				
	C9	Nicodemus, F., "Directional Reflectance and Emissivity of an Opaque Surface," <u>Applied Optics</u> , Volume 4, No. 7, July 1965, pps. 767-773				

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